

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-270165

(43)Date of publication of application : 27.09.1994

(51)Int.Cl. B29C 39/10  
B29C 39/44  
G02B 1/04  
G03H 1/18  
G11B 7/26  
G11B 11/10  
// B29C 67/00  
B29L 7:00

(21)Application number : 05-058444 (71)Applicant : DAINIPPON PRINTING CO LTD

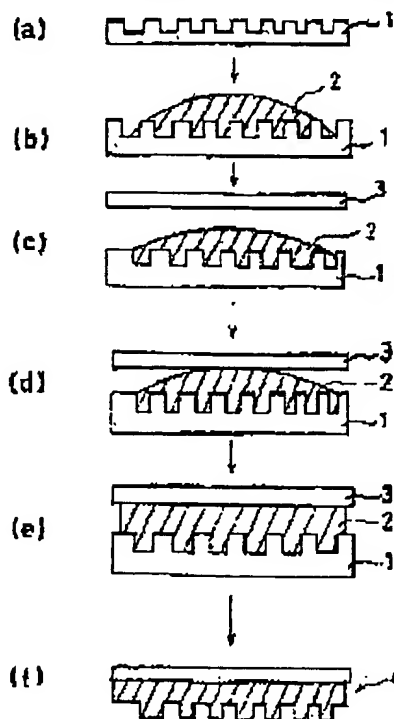
(22)Date of filing : 18.03.1993 (72)Inventor : SEGAWA TOSHIICHI

## (54) METHOD OF DUPLICATING MOLDED FORM HAVING UNEVEN PATTERN

### (57)Abstract:

PURPOSE: To obtain a duplicating plate capable of being controlled to the dimensions of an uneven pattern required as a product by controlling the temperature and moisture at the time of keeping an original plate in custody and also controlling the dimensions of an uneven pattern of a duplicating plate having a fundamental plate in duplication by a method of 2P having a curing type resin composite used therein.

CONSTITUTION: The duplicating method of 2P having a curing type resin composite 2 employed therein for a molded form 4 having an uneven pattern utilizing a resin plate as an original plate 1 is carried out such that, at first, on the original plate 1 formed with an uneven pattern, a curing type resin composite 2 is permitted to drop, and a fundamental plate 3 is lamination- laid on the resin composite 2 to be pressed. Next, by irradiating ionization radiation rays such as ultraviolet rays from the side of the fundamental plate 3 in order to cure the resin composite 2, and the resin composite 2 and fundamental plate 3 integrated with each other are separated from the original plate 1 side so as to duplicate the molded product 4. At the time of effecting duplication by a method of 2P having the curing type resin composite 2 used therein, the dimensions of an uneven pattern of duplicated plate having the fundamental plate 3 is controlled by adjusting the temperature and moisture



BEST AVAILABLE COPY

during the period of having custody of the original plate 1.